

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	14706	(high adj density adj plasma) or HDP	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/20 14:04
S2	2081	((high adj density adj plasma) or HDP) with (silicon with oxide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/20 14:05
S3	140	S2 and (cool\$3 with (substrate or wafer))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/20 15:51
S4	1	("6737328").PN.	USPAT	OR	OFF	2005/10/20 14:33
S5	15258	(silicon with oxide) and plasma and cool\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/20 15:52
S6	2971	(silicon with oxide with plasma) and cool\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/20 15:52
S7	100	silicon with oxide with plasma with cool\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/20 16:28
S8	0	(silicon with oxide) with high with density with plasma with cool\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/20 15:53
S9	1	("6045877").PN.	USPAT	OR	OFF	2005/10/20 16:28

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	2	((high adj density adj plasma) and (substrate or wafer) and (plasma with gas) and (cool\$3 with substrate) and ((substrate or wafer) with temperature)).CLM.	US-PGPUB	OR	ON	2005/10/24 13:21
L2	0	((high adj density adj plasma) and (substrate or wafer) and (plasma with gas) and (cool\$3 with substrate) and ((substrate or wafer) with temperature) and (silicon with oxide)).CLM.	US-PGPUB	OR	ON	2005/10/24 13:21
L3	1	((high adj density adj plasma) and (substrate or wafer) and (plasma with gas) and (cool\$3 with substrate) and ((substrate or wafer) with temperature) and (silicon with \$3oxide)).CLM.	US-PGPUB	OR	ON	2005/10/24 13:22